

11/15/2010

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re the Application of: **Miwa KOZAWA et al.**

Art Unit: **1795**

Application Number: **10/720,097**

Examiner: **Daborah Chacko Davis**

Filed: **November 25, 2003**

Confirmation Number: **4454**

For: **PROCESS FOR FORMING RESIST PATTERN, SEMICONDUCTOR DEVICE  
AND FABRICATION THEREOF**

Attorney Docket Number: **032132**

Customer Number: **38834**

**RESPONSE UNDER 37 C.F.R. §1.116**  
**EXPEDITED PROCESSING REQUESTED**

**MAIL STOP AF**

October 29, 2010

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Sir:

In response to the Office Action dated August 4, 2010, Applicant amends the claims as follows and submits the following remarks.

Amendments to the Claims begin on page 2 of this paper.

Remarks/Arguments begin on page 7 of this paper.